

U.S. Department of Commerce, Patent and Trademark Office <div style="display: flex; align-items: center;"> <div> LIST OF RELEVANT ART CITED BY APPLICANT (Use several sheets if necessary) </div> </div>					Docket No.: 6353/P1/DSM/LOW K/JW		Serial No.: 10/759,801		
Applicant(s): Howard Li, et al.					Filing Date: January 16, 2004			Group: 1763 Unknown	

U.S. Patent Documents							
*Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	3,156,073	11/10/64	Strasbaugh	451	162	
	AB	3,564,776	02/23/71	Aspden	451	4	
	AC	3,691,694	09/19/72	Goetz et al.	451	288	
	AD	3,603,042	09/07/71	Boettcher	451	269	
	AE	3,693,301	09/26/72	Lemaitre	451	58	
	AF	5,427,878	06/27/95	Corliss	430	30	
	AG	6,051,113	04/18/00	Moslehi	204	192.12	
	AH	6,086,734	07/11/00	Harada	204	298.03	
	AI	6,120,641	09/19/00	Stevens et al.	156	345.22	
	AJ	6,143,126	11/07/00	Stevens	156	345.22	
	AK	6,166,801	12/26/00	Dishon et al.	355	27	

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	AL	61164773A2	07/25/86	Japan		Abstract Only		
	AM	61188071A	08/21/86	Japan		Abstract Only		
	AN	61244460	10/30/86	Japan		Abstract Only		
	AO	61265262A	11/25/86	Japan		Abstract Only		
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	AR IBM Technical Disclosure Bulletin: "Dry Point Detection System," Dec. 1976, pp. 2507-2509
	AS IBM Technical Disclosure Bulletin: "Making Tunnel Barrier Layers by Plasma Deposition," Aug. 1979, p. 1194
	AT IBM Technical Disclosure Bulletin: "Apparatus for Locating Particles on a Blank Wafer in a Scanning Electron Microscope", May 1984, pp. 6609-6610
Examiner:	Date Considered: 1/23/6

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DB	AA	5,655,110	08/05/97	Krivokapic et al.	716	19	
	AB	5,657,254	08/12/97	Sierk et al.	702	98	
	AC	5,866,437	02/02/99	Chen et al.	438	14	
	AD	5,917,919	06/29/99	Rosenthal	381	71.11	
	AE	5,926,690	07/20/99	Toprac et al.	438	17	
	AF	6,161,054	12/12/00	Rosenthal et al.	700	121	
	AG	6,197,604 B1	03/06/01	Miller et al.	438	14	
	AH	6,208,751 B1	03/27/01	Almogly	382	149	
	AI	6,230,069 B1	05/08/01	Campbell et al.	700	121	
	AJ	6,245,581 B1	06/12/01	Bonser et al.	438	8	
V	AK	6,284,622 B1	09/04/01	Campbell et al.	438	424	

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	AN	569311A	03/23/93	Japan			Abstract Only	
	AO	639704A	02/15/94	Japan			Abstract Only	
V	AP	WO 98/02910	01/22/98	PCT				

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DB	AR	IBM Technical Disclosure Bulletin: "Auto-Defect Detection/Visual Defect Review Inspection System," Feb. 1989, pp. 306-307					
	AS	IBM Technical Disclosure Bulletin: "Dual Microscope Semiconductor Wafer Inspection Machine," March 1989, pp. 474-479					
	AT	IBM Technical Disclosure Bulletin: "Integrated Semiconductor Processing Facilitation by Mobile Ion Gettering During and After Resist Strip," May 1989, pp. 295-297					

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	AB	6,388,253 B1	05/14/02	Su	250	310	
	AC	6,405,096 B1	06/11/02	Toprac et al.	700	121	
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	AS	IBM Technical Disclosure Bulletin: "Multiprocessor and Multitasking Architecture for Tool Control of the Advanced via Inspection Tools," May 1992, pp. 190-191
	AT	The Novascan 210, "Integrated On-Line Thickness Monitoring System for CMP Applications", downloaded from http://www.nova.co.il.scan.htm on 9/10/96

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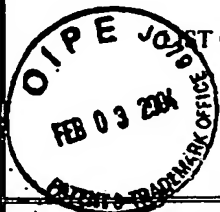
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


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	AS	Applied Materials Press Release Archive 1998 "Applied Materials Announced First Process Sequence Integration Product: The Copper Interconnect ESS," downloaded from http://www.appliedmaterials.com/newsroom/pr-00169.html on 3/12/02
	AT	J. Fraser, "Treating Software Strategically: Beyond Traditional MES," Semiconductor International, January 1999
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	AR	J. Bruchez et al., "European Suppliers Focusing on Tool Productivity," Semiconductor International, April 1999
	AS	J. Baliga, "Advanced Process Control: Soon to be A Must," Semiconductor International, July 1999
	AT	J. Baliga, "How Advanced Are We?," Semiconductor International, July 1999
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AS	T. Zavec et al., "Life Beyond Mix-and-Match: Controlling Sub-0.18 um Overlay Errors", Semiconductor International, July 2000
AT	F. Poag et al., "Implementing on-line ADC and an Automated Yield Information Management System," MICROmagazine.com, July, 2000

Examiner: *[Signature]* Date Considered: 1/23/06

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	AR	A. Toprac et al., "Run-to-Run Control of Shallow Trench Isolation Etch," AEC/APC 2000						
	AS	N. Patel, "Mix Issues in Process Control," Sematech AEC/APC Symposium XII, September 25, 2000						
	AT	J. Holden et al., "Characterizing a CVD-Integrated Metrology System," Semiconductor International, October 2000						
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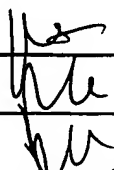
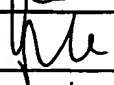
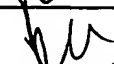
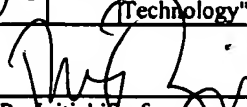
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<div style="font-size: 2em; font-family: cursive;">he</div>	<div style="font-size: 2em; font-family: cursive;">he</div>	<div style="display: flex; justify-content: space-between;"> <div>Examiner: <u>[Signature]</u></div> <div>Date Considered: <u>1/23/06</u></div> </div>

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	AR Nanometrics' NanoSpec 9000 Series Integrated Metrology Systems, downloaded from http://www.nanometrics.com/ProductsIntegrated.htm on 9/17/01
	AS "Applied Materials Launches Industry's First In-Line Metrology SEM System with 3D Imaging," Jan 10, 2000, downloaded from http://www.semiseek.com/News/press_release55.html
	AT Solid State Technology; Claasen-Vujicic et al; "Analysis of a 200/300mm Vertical Furnace with Integrated Technology"; April 2001; pps. s6, s8, s12
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	US-3	6,213,848 B1	04/10/01	Campbell et al.	700	1	
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